

IN SITU ELECTROSTATIC DISCHARGE DEPOLARIZATION  
USING HIGH DENSITY PLASMA

ABSTRACT OF THE DISCLOSURE

A method for electrostatic discharge depolarization is implemented. The buildup of charge on tool structures in fabrication tools for semiconductor processing may be expected to be of concern whenever high voltage is employed near the structure in a tool. The process herein includes selectively exposing the structure to a plasma for a selected time interval. The duration of the exposure time interval is sufficient to reduce the polarization of the structure whereby the forces due to the polarization do not interfere with the transport or movement of a wafer being processed.

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